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Elastic Differential Cross Sections for C₄F₆ by Low Energy Electron Impact KAZUTOSHI ANZAI, DAISUKE SUZUKI, MIZUHA OHKAWA, KAZUAKI NAGUMO, HIDETOSHI KATO, MASAMITSU HOSHINO, DAISUKE MOGI, TAKASHI TANIOKA, PAULO LIMAO-VIEIRA, HIROSHI TANAKA, SOPHIA UNIVERSITY TEAM, TOKYO UNIVERSITY OF SCINECE COLLAB-ORATION, KANTO DENKA KOGYO CO., LTD COLLABORATION, UNIVER-SIDADE NOVA DE LISBOA COLLABORATION — We report on the first measurements of elastic differential cross sections (DCSs) in C₄F₆ molecules by low energy electron impact. C_4F_6 has three isomers, hexafluoro-1,3-butadiene $(1,3-C_4F_6)$, hexafluoro-2-butyne $(2-C_4F_6)$ and hexafluorocyclobutene $(c-C_4F_6)$. 1,3- C_4F_6 has been suggested as a potential plasma processing molecule to be used as a replacement to the traditional reactive etching gases, having a negligible global warming potential. The experimental set-up for DCSs consists of a crossed-beam method in conjunction with the relative flow technique . These measurements were performed at incident electron energies from 3–100 eV and scattering angles of 20–130 degrees, with an energy resolution of ~ 50 meV at FWHM. The elastic DCSs for two isomers 1,3-C₄F₆ and 2-C₄F₆ at low incident electron energy, shows some considerable differences. These will be presented in more detail at the conference.

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